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Correction: Formation of pure Cu nanocrystals upon post-growth annealing of Cu–C material obtained from focused electron beam induced deposition: comparison of different methods

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Correction

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In Figure 8 of the original article, the scale of the ordinate was wrong. The correct figure looks as follows:

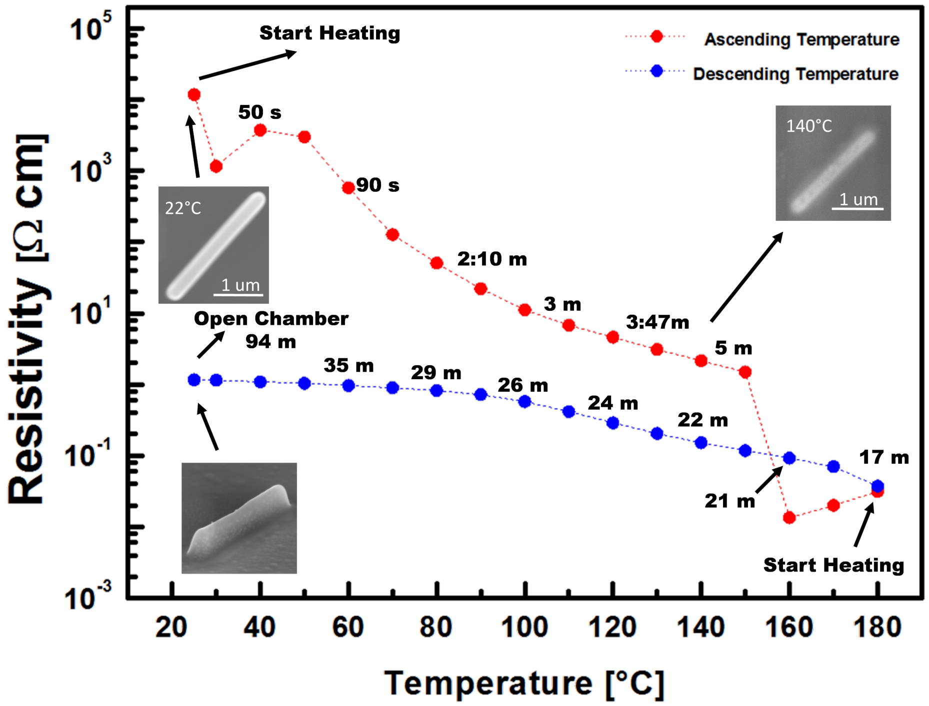

Figure 1: Figure 8 in the original article: Calculated resistivity from the resistance measurement of a Cu–C line during in situ post-growth heating with a hot plate (red dots) and cooling down (blue dots) inside the SEM chamber. The resistance did not change when opening the chamber. The top SEM images show the morphology changes of an adjacent FEBID line which was observed simultaneously during the in situ resistance measurement.

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